FIG. 1

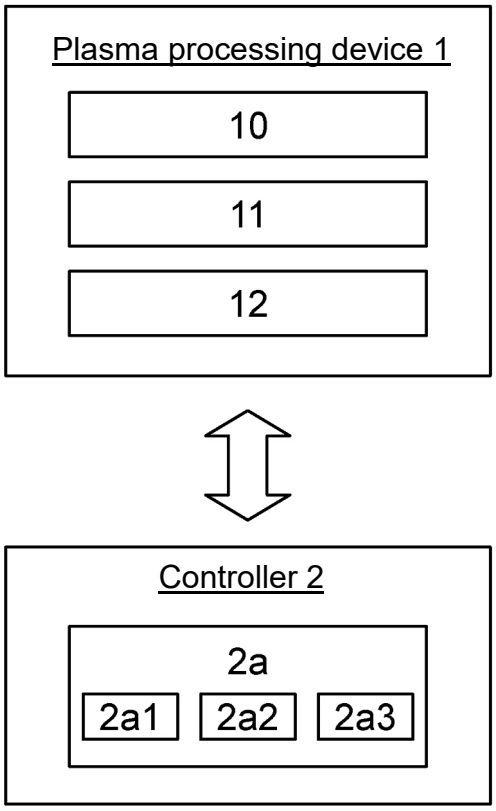

Plasma processing device 1
10
11
12
Controller 2
2a
2a1
2a2
2a3

FIG. 2

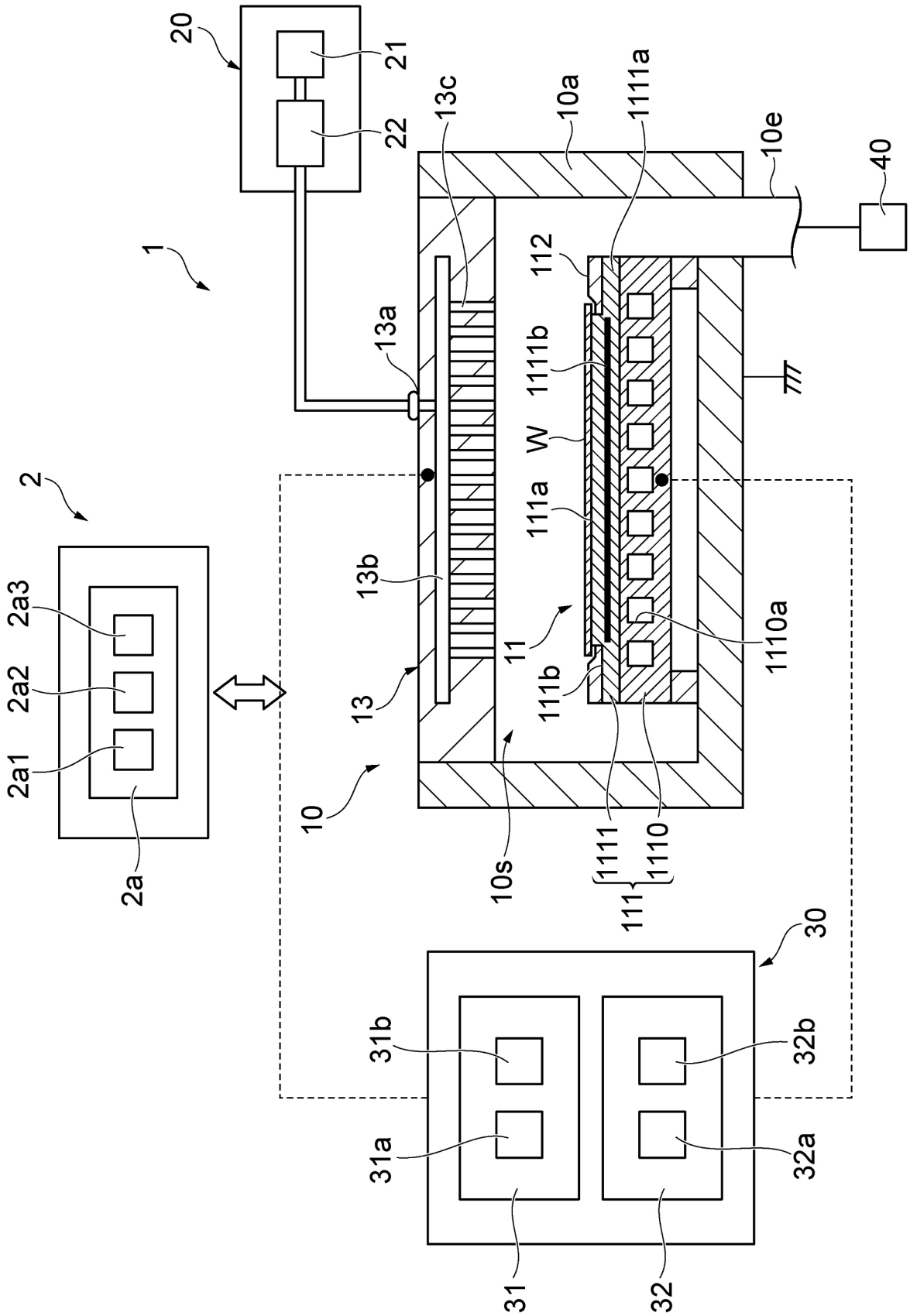

20
21
22
1
13c
10a
1111a
10e
40
112
13a
1111b
W
111a
13b
11
1110a
111b
13
10
10s
1111
1110
111
2
2a3
2a2
2a1
2a
30
31b
32b
31a
32a
31
32

FIG. 3

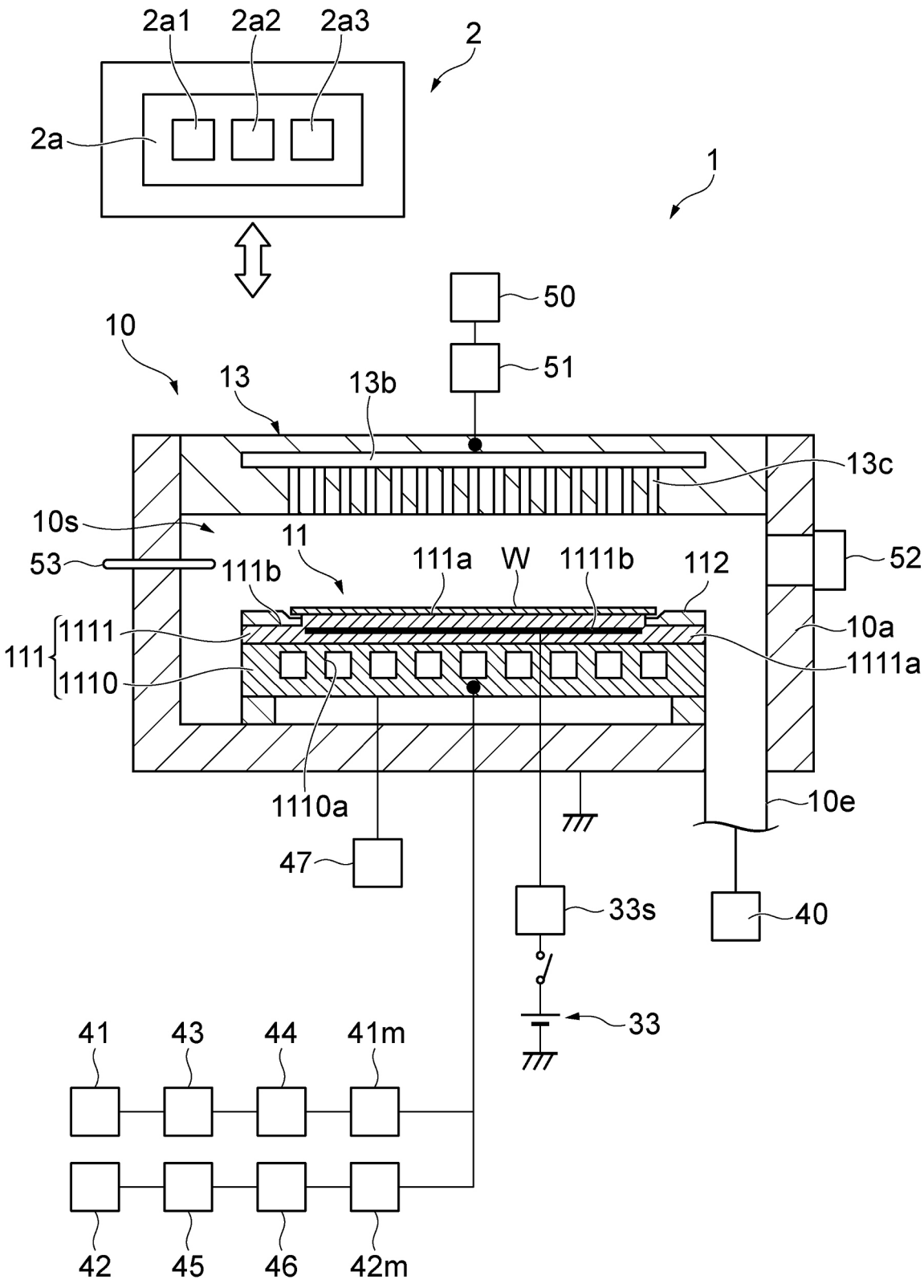

2a1
2a2
2a3
2
2a
1
50
51
10
13
13b
13c
10s
11
53
111b
111a
W
1111b
112
52
111
1111
1110
10a
1111a
1110a
10e
47
33s
40
33
41
43
44
41m
42
45
46
42m

FIG. 4

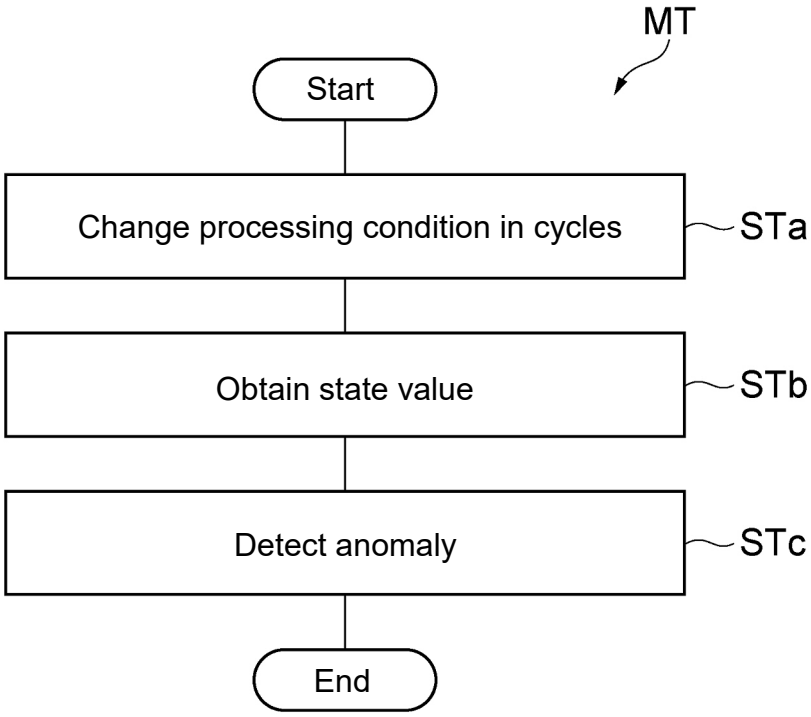

MT
Start
Change processing condition in cycles
STa
Obtain state value
STb
Detect anomaly
STc
End

FIG. 5

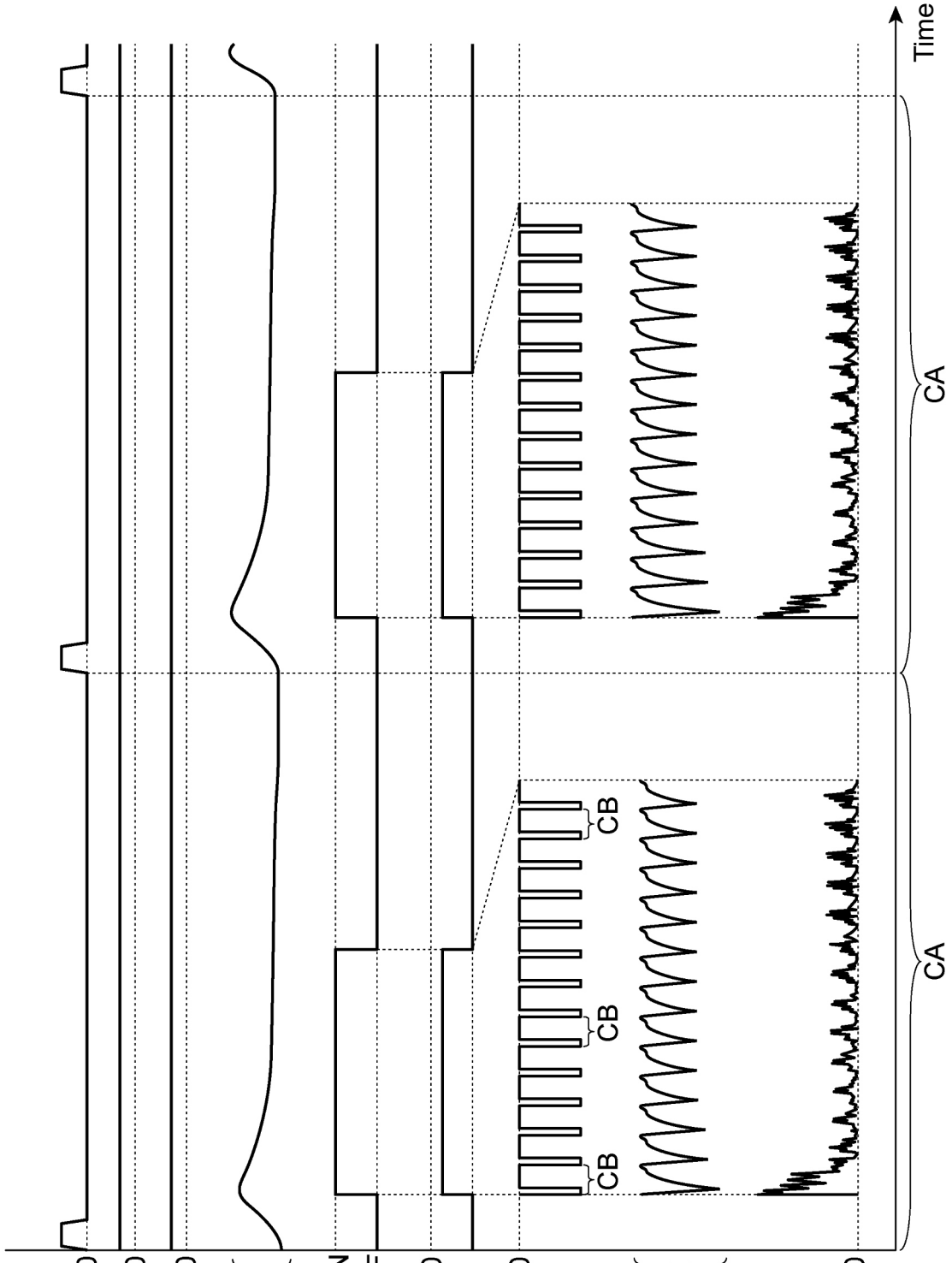
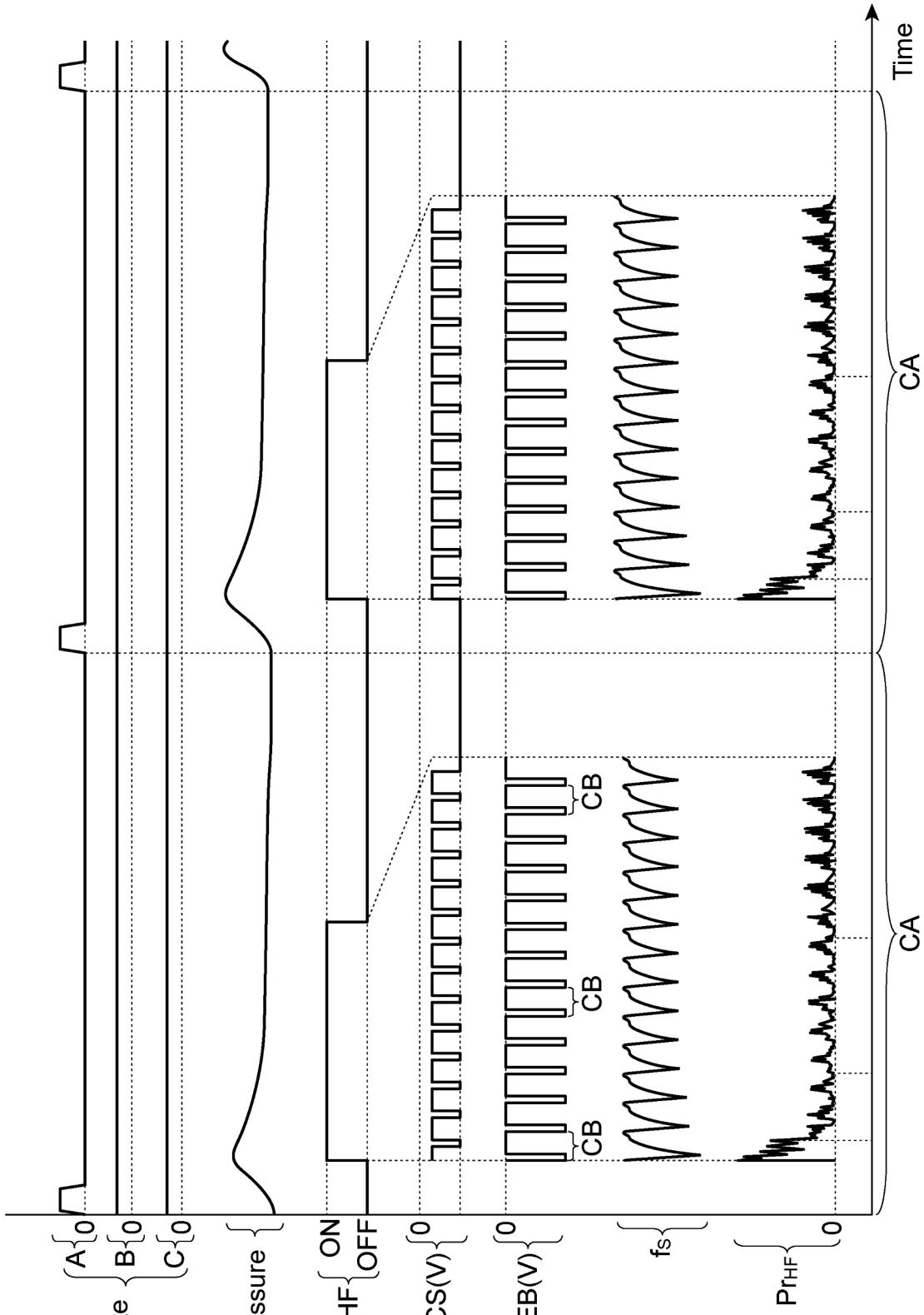

Flow rate
A
B
C
0
Pressure
HF
ON
OFF
DCS(V)
EB(V)
CB
CB
CB
f_S
Pr_{HF}
Time
CA
CA

FIG. 6


Flow rate
A
B
C
0
Pressure
HF
ON
OFF
DCS(V)
EB(V)
CB
CB
CB
f_S
Pr_{HF}
Time
CA
CA